

## Abstract

5        The present invention is directed to a precious metal  
sputtering target having a columnar crystallographic  
microstructure such that crystals are grown in a direction  
normal to the sputtering surface in order to solve  
conventional problems. The high-purity sputtering target of  
10 the present invention prevents chipping of a minute cluster  
mass that occurs in a sputtering target produced through  
casting or powder metallurgy; produces thin film of excellent  
quality; and has considerably reduced internal defects.

15